

β¹
composition comprising an over-coating resin derived from a mixture of acrylic acid, and an alkyl acrylate, a solvent, and a basic compound.

β²
6. (Amended Herein) The over-coating composition according to Claim 1, wherein said basic compound is selected from the group consisting of an amine compound and a hydroxide salt thereof; an amide compound; a urethane compound; and a mixture thereof.

β³
14. (Amended Herein) A process for forming a photoresist pattern, comprising the steps of:

- (a) coating a photoresist composition on a substrate to form a photoresist film;
 - (b) coating an over-coating composition on the upper portion of said photoresist film to form a over-coating, wherein said over-coating composition comprises an over-coating resin derived from a mixture of acrylic acid and an alkyl acrylate, a solvent, and a basic compound;
 - (c) exposing said over-coated substrate to light using a light source; and
 - (d) developing said exposed over-coated substrate.
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REMARKS

Claims 1-21 are pending in this application. Claims 1, 6 and 14 have been amended. Claims 14-20 have been withdrawn from further consideration by the Examiner.

Attached hereto as Appendix A captioned "Version with Markings to show changes made" is a marked-up version of the changes made to the claims by the current amendment. In addition, for the convenience of the Examiner, all claims now pending following entry of the present Amendment and Response are reproduced in Appendix B captioned "Pending Claims."